

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	7	(Itoh and Higuchi and Sakai and Honda and Takai and Okazaki and Inaba).in.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/11 09:50
S10	28	(118/726 or 118/715 or 118/723).ccls. and ionizing and resistive heating	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/11 10:57
S11	38	(118/726 or 118/715 or 118/723).ccls. and (electron beam or EB) and resistive heating	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/11 11:00
S12	113	(118/726 or 118/715 or 118/723).ccls. and (vapor ADJ5 (electron beam or EB))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/11 11:05
S13	127	(118/726 or 118/715 or 118/723).ccls. and ((vapor or gas) ADJ5 (electron beam or EB))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/11 11:06
S14	82	(118/726 or 118/715 or 118/723).ccls. and ((vapor or gas) ADJ5 (electron beam or EB)) and heating	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/11 11:07

S20	33	(apparatus or machine or device) and ((resistance ADJ2 heating and electron ADJ2 beam) ADJ2 evaporation ADJ2 source)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/12 16:10
S21	5	(apparatus or machine or device) and ((resistance ADJ2 heating and electron ADJ2 beam) ADJ2 evaporation ADJ2 source) and nozzle	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/12 16:12
S22	9	(apparatus or machine or device) and ((resistance ADJ2 heating and electron ADJ2 beam) ADJ2 evaporation ADJ2 source) and (bias or negative)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/12 16:23
S24	9	(apparatus or machine or device) and ((resistance ADJ2 heating and electron ADJ2 beam) ADJ2 evaporation ADJ2 source) and (bias or negative or minus)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/13 07:38

S25	15	(apparatus or machine or device) and ((resistance ADJ2 heating and electron ADJ2 beam) ADJ4 evaporation ADJ2 source) and (bias or negative or minus)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/13 07:48
S26	239	(apparatus or machine or device) and ((resistance ADJ2 heating or electron ADJ2 beam) ADJ4 evaporation ADJ2 source) and (bias or negative or minus)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/13 07:49
S27	212	(apparatus or machine or device) and ((resistance ADJ2 heating or electron ADJ2 beam) ADJ2 evaporation ADJ2 source) and (bias or negative or minus)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/13 07:49
S28	9	(apparatus or machine or device) and ((resistance ADJ2 heating or electron ADJ2 beam) ADJ2 evaporation ADJ2 source) and ((bias or negative or minus) adj2 (source or device))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/13 07:50

S30	65	(electron adj2 beam adj2 evaporation) and (resistance adj2 heating adj2 evaporation) and ((negative or bias) adj3 voltage)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/13 08:07
S31	7	(apparatus or machine or device) and ((resistance heating and electron beam) evaporation source) and (nozzle or tube or port)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/13 10:05
S32	12	(apparatus or machine or device) and ((resistance ADJ2 heating and electron ADJ2 beam) ADJ2 evaporation ADJ2 source) and (nozzle or tube)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/13 10:09

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